Kaushini Wickramasinghe et al., Growth and Characterization of Bi<sub>2</sub>Se<sub>3</sub> and Sb<sub>2</sub>Te<sub>3</sub> Grown by Molecular Beam Epitaxy on In<sub>2</sub>Se<sub>3</sub> Layers Grown via Selenium Passivation of InP(111)B Substrates

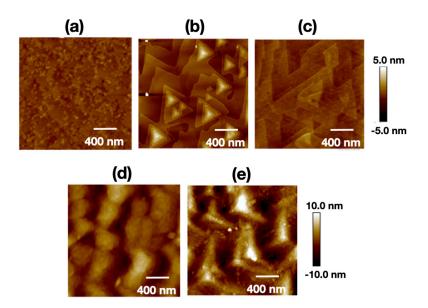


Figure 1. AFM of (a). In<sub>2</sub>Se<sub>3</sub> layer grown via selenium passivation of InP(111)B substrates at a temperature of  $T_{sub}$  =480 °C with a rms = 0.4 nm . AFM of Bi<sub>2</sub>Se<sub>3</sub> layers grown at a substrate temperature of: (b).  $T_{sub}$  =240 °C with rms = 1.0nm and (c).  $T_{sub}$  =295 °C with rms of 0.6 nm. (d) AFM of Sb<sub>2</sub>Te<sub>3</sub> layer grown at ,  $T_{sub}$  =230 °C, and (e) AFM of Sb<sub>2</sub>Te<sub>3</sub>/Bi<sub>2</sub>Se<sub>3</sub> superlattice grown at  $T_{sub}$  =240 °C with rms = 3.45 nm.

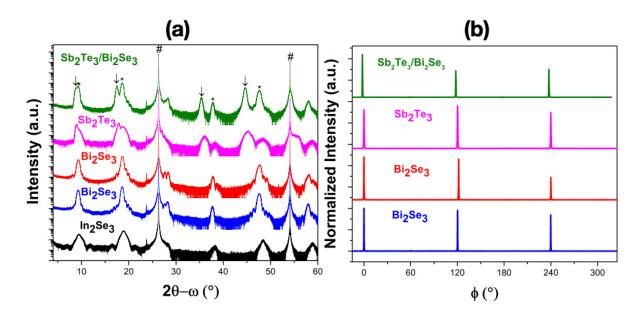


Figure 2. (a) HR-XRD of In<sub>2</sub>Se<sub>3</sub>, Bi<sub>2</sub>Se<sub>3</sub>, Sb<sub>2</sub>Te<sub>3</sub> and Sb<sub>2</sub>Te<sub>3</sub>/Bi<sub>2</sub>Se<sub>3</sub> superlattice of the samples shown in the AFM. Bi<sub>2</sub>Se<sub>3</sub> is grown at a substrate temperature of  $T_{sub}$  =240 °C, Bi<sub>2</sub>Se<sub>3</sub> is grown at a substrate temperature of  $T_{sub}$  =240 °C, Bi<sub>2</sub>Se<sub>3</sub> is grown at a substrate temperature of  $T_{sub}$  =240 °C. The '#', ' $\downarrow$ ', and '\*' indicate the substrate peak, Sb<sub>2</sub>Te<sub>3</sub> peak, and Bi<sub>2</sub>Se<sub>3</sub> peak respectively. (b).  $\Phi$  scans of the (015) plane shows complete suppression of twin domains.